

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	2550	(438/627,687).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/02 10:44
L3	1496	I2 and diffusion same barrier	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/02 10:45
L4	36	I2 and (diffusion same barrier) and interconnect and ((partial\$2 near10 (etch\$3 or remov\$3)) near10 barrier)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/02 10:47
L5	6	I4 and (barrier near10 remain\$3) same bottom same (via or contact or hole or trench)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/02 10:50
S69	21788	438/6,10,104,107,108,109,110,111, 112,113,114,118,121,122,123,128, 129,135,142,145,149,151,157,176, 478,184,193,195,196,197,198,200, 201,202,203,206,207,209,210,211, 218,237,165,294,308,337,353,378, 401,410.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/13 08:38
S70	182273	"438"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/02 10:43
S71	23457	438/6,10,104,107,108,109,110,111, 112,113,114,118,121,122,123,128, 129,135,142,145,149,151,157,176, 478,184,193,195,196,197,198,200, 201,202,203,206,207,209,210,211, 218,237,165,294,308,337,353,378, 401,410.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 21:02

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S72	190610	"438"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 21:13
S73	1118	S72 and (pvd or (vapor same deposition)) and (position or align or alignment) same (wafer or layer) and (resist or photoresist) and (formula or equation or algorith\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 23:32
S74	171	S73 and lithographic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 23:33
S77	7	S74 and (position or align or alignment) same (shift or move or movement or change or alter or alteration) same (formula or equation or algorith\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 23:36
S78	3	(US-20040197939-\$ or US-20040058540-\$ or US-20030064422-\$).did.	US-PGPUB	OR	ON	2006/09/26 00:26
S79	190740	"438"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 10:43
S80	1118	S79 and (pvd or (vapor same deposition)) and (position or align or alignment) same (wafer or layer) and (resist or photoresist) and (formula or equation or algorith\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:33
S86	3	(US-20040197939-\$ or US-20040058540-\$ or US-20030064422-\$).did.	US-PGPUB	OR	ON	2006/09/26 11:59
S88	3	S86 and (position or align or alignment) same (shift or move or movement or change or alter or alteration)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 12:23

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S96	2	S86 and (thin same film) same (resist or photoresist)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:35
S97	2	S96 and lithographic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:37